Title (en)

LARGE AREA NANOPATTERNING METHOD AND APPARATUS

Title (de)

VERFAHREN UND VORRICHTUNG ZUR GROSSFLÄCHIGEN NANOSTRUKTURIERUNG

Title (fr)

PROCÉDÉ ET APPAREIL DE FORMATION DE NANOMOTIF DE GRANDE SUPERFICIE

Publication

EP 2238608 A4 20120222 (EN)

Application

EP 08871196 A 20081118

Priority

- US 2008012901 W 20081118
- US 1186108 P 20080122

Abstract (en)

[origin: WO2009094009A1] Embodiments of the invention relate to methods and apparatus useful in the nanopatterning of large area substrates, where a rotatable mask is used to image a radiation- sensitive material. Typically the rotatable mask comprises a cylinder. The nanopatterning technique makes use of Near-Field photolithography, where the mask used to pattern the substrate is in dynamic contact with the substrate. The Near-Field photolithography may make use of an elastomeric phase-shifting mask, or may employ surface plasmon technology, where a rotating cylinder surface comprises metal nano holes or nanoparticles.

IPC 8 full level

H01L 21/027 (2006.01)

CPC (source: EP KR)

B29C 33/424 (2013.01 - EP); **G03F 1/50** (2013.01 - EP); **G03F 1/60** (2013.01 - EP KR); **G03F 1/62** (2013.01 - KR); **G03F 7/20** (2013.01 - EP KR); **G03F 7/2014** (2013.01 - EP KR); **G03F 7/24** (2013.01 - EP KR); **H01L 21/0274** (2013.01 - KR)

Citation (search report)

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- [Y] US 2007200276 A1 20070830 - MACKEY JEFF [US], et al
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- See references of WO 2009094009A1

Designated contracting state (EPC)

AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MT NL NO PL PT RO SE SI SK TR

DOCDB simple family (publication)

WO 2009094009 A1 20090730; AU 2008348353 A1 20090730; CA 2709718 A1 20090730; CN 101911249 A 20101208; CN 105171985 A 20151223; EP 2238608 A1 20101013; EP 2238608 A4 20120222; JP 2011526069 A 20110929; JP 5102879 B2 20121219; KR 20110008159 A 20110126; MX 2010007954 A 20101105; RU 2010134893 A 20120227; RU 2488188 C2 20130720; TW 200932666 A 20090801; TW I518027 B 20160121

DOCDB simple family (application)

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